

LP-CVD Tempress TS-61004-4



Beladestation mit Steuerrechner

Kenngößen:

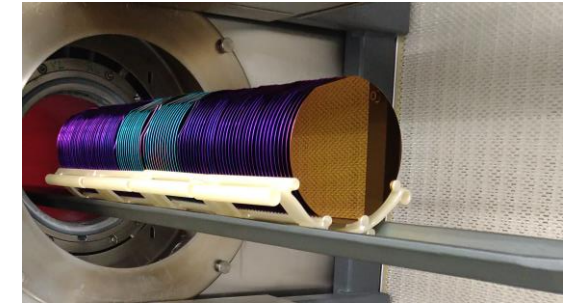
- Refurbishment und Inbetriebnahme im Jahr 2000
- Wafergröße: 100 mm
- 4 Rohre mit je 3 Heizzonen
- Länger der Flat Zone (Temperaturregelung auf +/- 0,5 °C): 95-100 cm
- Anzahl Wafer pro Fahrt: 50-100
- Höhe: 2455 mm
- Gewicht: Beladestation: ca. 800 kg, Gassteuereinheit: ca. 1000 kg, Ofeneinheit: ca. 1500 kg
- Stromanschluss: 380V, 50Hz, 5 Phasen

Prozesse:

- Rohr 1: High-Temperature Oxide (HTO) / Siliziumnitrid (SiN)
- Rohr 2: High-Temperature Oxide (HTO) / Siliziumnitrid (SiN)
- Rohr 3: Polysilizium
- Rohr 4: Low-Temperature Oxide (LTO) / Phosphor-Silikatglas (PSG)

Bestandteile:

- Ofenteil
- Beladestation
- Gas Cabinet
- Steuerrechner



Ofenteil mit Gassteuereinheit

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Load station with control computer

Specifications:

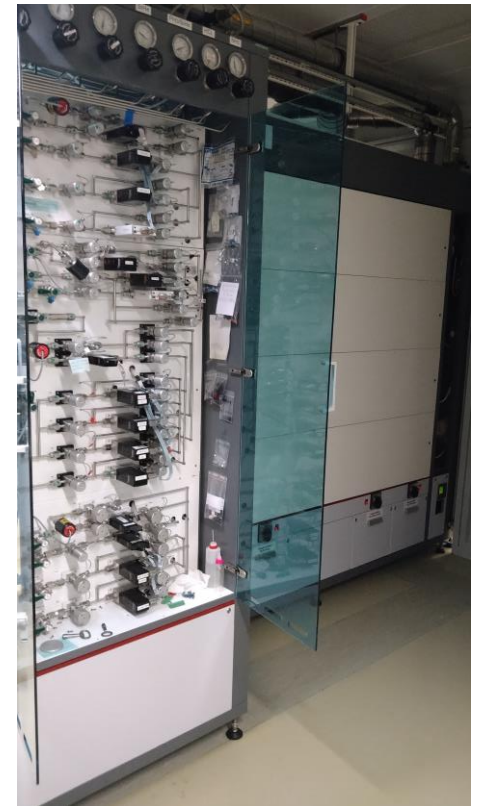
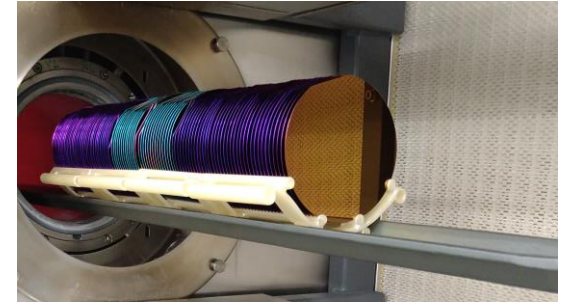
- Refurbishment and commissioning year 2000
- Wafer size: 100 mm
- 4 Tubes with 3 heating elements each
- Length of thermal flat zone : 95-100 cm, +/- 0,5 °C
- Number of wafers per run: 50-100
- Height: 2455 mm
- Weight: load station: ca. 800 kg, Gas-source-cabinet: ca. 1000 kg, furnace: ca. 1500 kg
- Power: 380V, 50Hz, 5 Wire

Processes:

- Rohr 1: high-temperature oxide (HTO) / silicon nitride (SiN)
- Rohr 2: high-temperature oxide (HTO) / silicon nitride (SiN)
- Rohr 3: polysilicon
- Rohr 4: low-temperature oxide (LTO) / phosphorous-silicate glass (PSG)

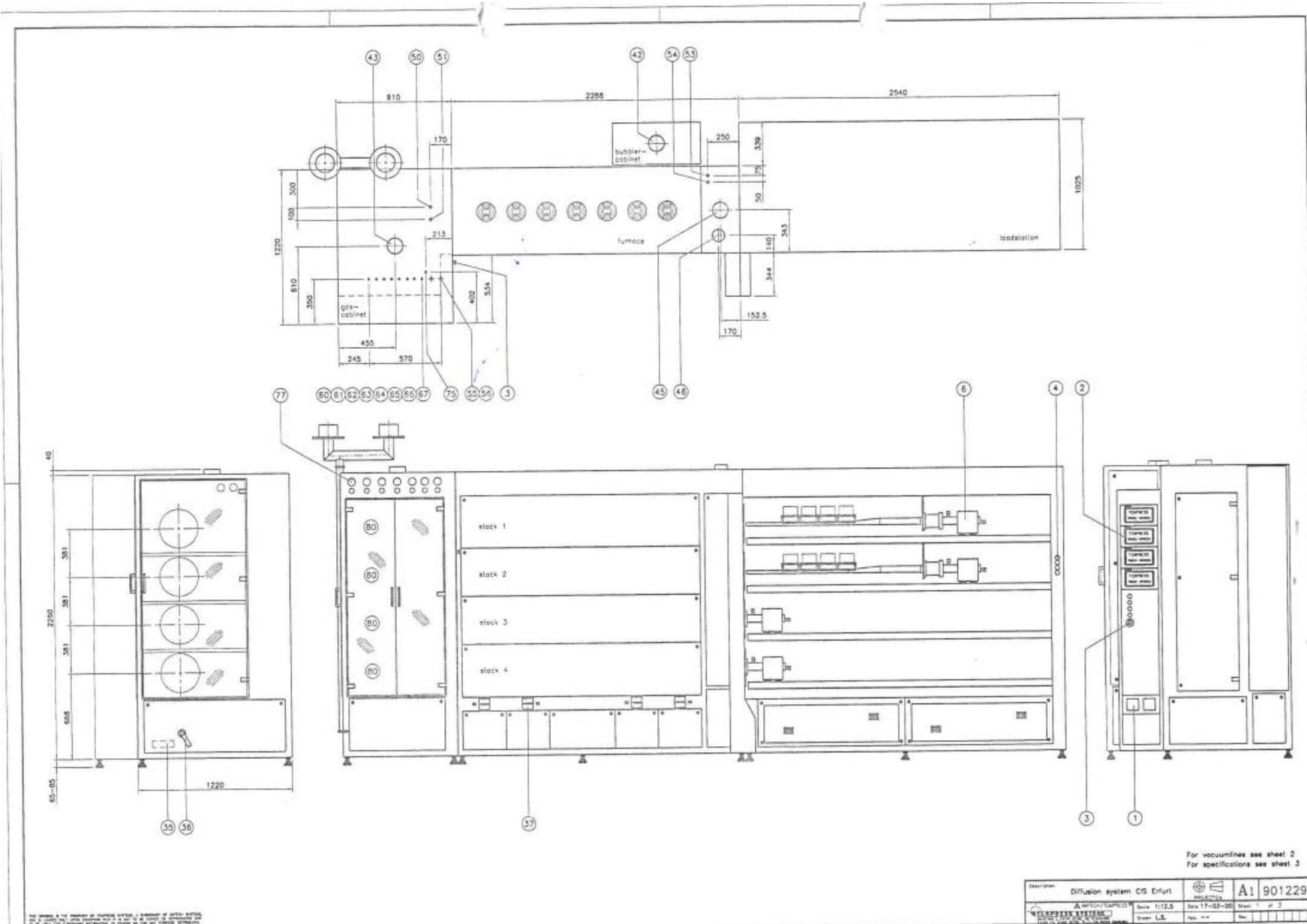
Main parts:

- Furnace
- Load station
- Gas Cabinet
- Control computer



Furnace with MFC unit

LP-CVD Tempress TS-61004-4: Footprint



For volumines see sheet 2
For specifications see sheet 3

DESCRIPTION	Diffusion system C/S Erfurt	PROJEKT	A1 901229
SCALE	1:12.5	DATE	17-03-00
DESIGNER	L.S.	APP. NAME	